

FORM PTO-1449

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

Document Number (Optional)
3790/AF2/SB

Application Number
09/464,362

Applicant
Kurita, et al.

7017

(Use several sheets if necessary)

Sheet 1 of 2

Filing Date
December 15, 1999

Group Art Unit

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER							DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>SM</i>	4	1	7	8	1	1	3	12/11/79	Beaver, II, et al.			
<i>SM</i>	4	6	9	3	7	7	7	9/15/87	Hazano, et al.			
<i>SM</i>	4	7	5	9	6	8	1	7/26/88	Nogami			
<i>SM</i>	4	7	7	0	5	9	0	9/13/88	Hugues, et al.			
<i>SM</i>	4	7	8	5	9	6	2	11/22/88	Toshima			
<i>SM</i>	4	8	0	1	2	4	1	1/31/89	Zajac, et al.			
<i>SM</i>	4	8	2	8	2	2	4	5/9/89	Crabb, et al.			
<i>SM</i>	4	8	3	6	7	3	3	6/6/89	Hertel, et al.			
<i>SM</i>	4	8	6	3	5	4	7	9/5/89	Shidahara, et al.			
<i>SM</i>	4	9	2	3	5	8	4	5/8/90	Bramhall, Jr., et al.			
<i>SM</i>	4	9	5	2	2	9	9	8/28/90	Chrisos, et al.			
<i>SM</i>	4	9	9	0	0	4	7	2/5/91	Wagner, et al.			
<i>SM</i>	5	1	3	1	4	6	0	7/21/92	Krueger			
<i>SM</i>	5	1	8	6	7	1	8	2/16/93	Tepman, et al.			
<i>SM</i>	5	2	2	7	7	0	8	7/13/93	Lowrance			
<i>SM</i>	5	2	5	4	1	7	0	10/19/93	Devilbiss, et al.			
<i>SM</i>	5	2	6	1	9	3	5	11/16/93	Ishii, et al.			
<i>SM</i>	5	4	4	3	3	4	6	8/22/95	Murata, et al.			
<i>SM</i>	5	4	4	7	4	0	9	9/5/95	Grunes, et al.			
<i>SM</i>	5	4	6	4	3	1	3	11/7/95	Ohsawa			
<i>SM</i>	5	5	1	6	7	3	2	5/14/96	Flegal			
<i>SM</i>	5	6	1	1	6	5	5	3/18/97	Fukasawa, et al.			
<i>SM</i>	5	6	1	5	9	8	8	4/1/97	Wiesler, et al.			
<i>SM</i>	5	6	5	5	2	7	7	8/12/97	Galdos, et al.			
<i>SM</i>	5	7	3	8	7	6	7	4/14/98	Coad, et al.			
<i>SM</i>	5	9	0	9	9	9	4	6/8/99	Blum, et al.			
<i>SM</i>	6	0	3	4	0	0	0	3/7/00	Heyder, et al.			
<i>SM</i>	6	0	7	9	6	9	3	6/27/00	Ettinger, et al.			

EXAMINER

DATE CONSIDERED 4/2/01

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IN AN APPLICATIONApplicant
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Sheet 2 of 2

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FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER							DATE	COUNTRY	CLASS	SUBCLASS	Translation	
												Full	Abstract
<i>syn</i>	9	9	1	8	6	0	3	4/15/99	PCT			X	
<i>syn</i>	9	9	5	9	9	2	8	11/25/99	PCT			X	
<i>syn</i>	9	9	6	0	6	1	0	11/25/99	PCT			X	
<i>syn</i>	9	9	6	0	6	1	1	11/25/99	PCT			X	
<i>syn</i>	9	9	6	0	6	1	2	11/25/99	PCT			X	
<i>syn</i>	9	9	6	1	3	5	0	12/2/99	PCT			X	
<i>syn</i>	0	6	0	7	7	9	7	7/27/94	EP			X	
<i>syn</i>	1	0	2	8	9	3	3	1/31/89	JP				X
<i>syn</i>	2	1	5	2	2	5	1	6/12/90	JP				X
<i>syn</i>	3	2	7	4	7	4	6	12/5/91	JP				X
<i>syn</i>	4	0	9	8	8	4	8	3/31/92	JP				X
<i>syn</i>	4	2	4	0	7	2	1	8/28/92	JP				X
<i>syn</i>	5	0	1	3	5	5	1	1/22/93	JP				X
<i>syn</i>	5	2	8	3	5	0	0	10/29/93	JP				X
<i>syn</i>	6	1	0	4	3	2	6	4/15/94	JP			X	
<i>syn</i>	6	1	5	6	6	2	4	6/3/94	JP				X
<i>syn</i>	6	1	6	3	5	0	5	6/10/94	JP				X

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>syn</i>	EP 97103323.8 Search issued 10/6/98 (Atty Dkt. 1063/4593)
<i>syn</i>	Iscoff, Ron, ed. "Dry Etching Systems: Gearing Up for Larger Wafers," Semiconductor International, Oct. 85, pp. 49-60.
<i>syn</i>	Declaration of Thomas B. Brezocsky dated 1/29/99
<i>syn</i>	US 08/627,532 filed 4/4/96 (Atty Dkt. 1057/4594)
<i>syn</i>	US 08/640,708 filed 3/4/96 (Atty Dkt. 1063/4593)
<i>syn</i>	US 08/946,922 filed 10/8/97 (Atty Dkt. 2253)
<i>syn</i>	US 09/082,483 filed 5/18/98 (Atty Dkt. 2253: CIP)

EXAMINER *syn*

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